IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applica	ation of:) PATENT APPLICATION	ON
Inventors:	Jer-Shen Maa, Jong-Jan Lee, Douglas J. Tweet and Sheng Teng Hsu)))	
Serial No.:	Not Yet Assigned) Attorney Docket No.) SLA 0749	
Filed:	Herewith)))	
Title:	METHOD OF FORMING RELAXED SIGE LAYER)	

Honorable Commissioner for Patents Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Sir:

Listed on attached Form PTO-1449 is information submitted pursuant to 37 C.F.R. §1.56. A copy of each listed publication is submitted herewith.

Applicant respectfully requests that the listed information be considered by

the Examiner and made of record in the above-identified application.

Respectfully submitte

Reg. No. 27,672

David C. Ripma, Patent Counsel Sharp Laboratories of America, Inc.

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1449A/PTO U.S. Department of Commerce Rev. 10/95 Patent and Trademark Office				Complete If Known		
		Application Number				
LIST OF PRIOR ART CITED				Filing Date	07-22-03	
BY APPLICANT				First Named Inventor	Jer-shen Maa	
				Group Art Unit		
(use as many sheets as necessary)			necessary)	Examiner Name		
Sheet	1	of	2	Attorney Docket No.	SLA.0749	

	U.S. PATENT DOCUMENTS						
Examiner Initials	Cite No.¹	U.S. Patent Document Kind Number Co (if know	Name of Patentee or Applicant de ² of Cited Document wn)	Date of Publication of Cited Document MM-DD-YY	Pages, Columns, Lines, Where Relevant Passages or Figures Appear		
-		6,562,703 B1	Maa et al.	05-13-03			
		6,464,780 B1	Manti et al.	10-15-02			
		6,486,008 B1	Lee	11-26-02			
		5,877,070	Goesele et al.	03-02-99			

FOREIGN PATENT DOCUMENTS						
	Cite	Foreign Patent Dcument	Name of Patentee or Applicant	Date of Publication of Cited Document	Pages, Columns, Lines, Where Relevant	Ţ⁵
		Office ³ Number⁴ Kind Code ⁵	of Cited Document	MM-DD-YY	Passages or Figures Appear	

OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.				
		G.F. CEROFOLINI et al., Hydrogen-related Complexes as the Stressing Species in High-fluence, Hydrogen-implanted, Single-crystal Silicon, Physical Review B, vol. 46, p. 2061 (1992)			
		DEEPAK K. NAYAK et al., High-Mobility Strained-Si PMOSFETs, IEEE Transactions on Electron Devices, Vol. 43, 1709 (1996)			
		ADITYA AGARWAL et al., Efficient Production of Silicon-on-Insulator Films by Co-implantation of He ⁺ with H ⁺ , Proceedings of the 1997 IEEE International SOI Conference, p. 44, (1997).			

Examiner	Date	1
Signature	Considered	

Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Unique citation designation number. 2 See attached Kinds of U.S. Patent Documents. 3 Enter Office that issued the document, by the two letter code (WIPO Standard ST.3). 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 5 Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. 6 Applicant is to place a check mark here if English language Translation is attached

1449A/PTO	1449A/PTO U.S. Department of Commerce Rev. 10/95 Patent and Trademark Office		•	Complete If Known		
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(use as many sheets as necessary)			necessary)	Examiner Name		
Sheet	2	of	2	Attorney Docket No.	SLA.0749	

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, country where published, source.	T²
		M.K. WELDON et al., On the Mechanism of the Hydrogen-Induced Exfoliation of Silicon, J. Vac. Sci. Technol. B. 15, 1065, (1997)	
		S. MANTL et al., Strain Relaxation of Epitaxial SiGe Layers on Si(100) Improved by Hydrogen Implantation, Nuclear Instruments and Methods in Physics Research B 147, 29, (1999)	
		H. TRINKAUS et al., Strain Relaxation Mechanism for Hydrogen-Implanted $Si_{1-x}Ge_x/Si(100)$ Heterostructures, Appl. Phys. Lett., 76, 3552, (2000)	
		K. RIM et al., Strained Si NMOSFETs for High Performance CMOS Technology, 2001 Symposium on VLSI Technology Digest of Technical Papers, p. 59, (IEEE 2001)	
		JASON T.S. LIN et al., Nova Cut™ Process: Fabrication of Silicon-on Insulator Materials, 2002 IEEE International SOI Conference, Williamsburg, Virginia, (2002)	
		M. LUYSBERG et al., Effect of helium ion implantation and annealing on the relaxation behavior of pseudomorphic $Si_{l,x}Ge_x$ Buffer Layers on $Si(100)$ substrates, Journal of Applied Physics, Vol. 92, No. 8 (2002)	
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Examiner	Date	
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